

UCID--21966

DE90 007926

February 8, 1990

SUBKILOVOLT RESPONSE OF KODAK T max XUV FILM

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Introduction:

A calibration of Kodak T max 100 XUV film at six x-ray energies ranging from 0.27 keV to 1.49 keV has been concluded. The primary purpose was to compare the sensitivity of this film to that of Kodak type 101-07 XUV film in order to appraise the feasibility of replacing the type 101-07 film with the type T max 100 film. In addition to being considerably less expensive, the T max 100 film is less disposed to abrasion from handling. A secondary objective was to provide a base for further response measurements should the T max 100 film prove to be an acceptable substitute for the type 101-07 film.

Instrumentation:

An x-ray source and spectrometer facility at the LBL Center for X-ray Optics in Berkeley provided the means for recording all x-ray exposures used for these measurements. The x-ray source is a water cooled Henke tube using interchangeable anodes selected to produce the desired characteristic emission. The anode is illuminated by electrons electrostatically focused onto each face of the V shaped emission surface. These electrons are produced by a tungsten filament hidden behind the anode to prevent contamination from tungsten evaporation on the emission faces of the anode. Under normal conditions, a period of about 1 hour is required to bring the system to atmosphere, change the anode, and return to a stable vacuum environment.

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The x-ray source housing is directly coupled to a vacuum pipe leading to an experimental chamber containing the spectrometer, camera and proportional counter. This chamber is also equipped with an x-ray shutter to block off the x-ray beam while changing film position between exposures. All movable components within the chamber are remotely controlled from outside the vacuum system. The spectrometer is described in detail in Reference 1¹. It features a removable elliptically curved crystal which can be precisely aligned to Bragg reflect line radiation from the source and focus the reflected beam at the aperture adjacent to the camera window slit. This slit is at the center of an arc which forms a circular tray holding the film. Thus, the Bragg reflected beam, focused at the slit produces a normal incident spectrum along the circular film channel. All measurements for this experiment were made using a lead stearate crystal ($2d=100\text{\AA}$). The camera box is a light-tight structure containing supply and take-up reels to move the 35mm film along the circular track. Depending on the film thickness, the camera will easily accommodate from 5 to 10 exposures.

Before or following a set of exposures, the camera was remotely translated out of the Bragg reflected beam to allow a proportional counter to view and record the spectrum by scanning along the circle at a pre-set rate. The exposure intensity in units of photons per square micrometer related to a film recorded spectral line is calculated from the measured peak count rate, counter efficiency and exposure time. Pre-measured geometry factors, (ratio of the proportional counter to film radii and slit dimensions) are entered as constants. Both camera and proportional counter are fitted with identical window material to eliminate the need for window attenuation corrections. X-ray tube and proportional counter parameters used in this experiment are given in Table 1.

All exposed film was taken to the L-division "Technical Photography Laboratory" at LLNL in Livermore for processing and analysis. The films were developed 8 minutes at 68°F in Kodak "T max developer" using agitation intervals of 5 seconds every 30 seconds. Following development, the film was sequentially transferred to a "Kodak Indicator" stop bath for 30

¹B.L. Henke, H.T. Tamada, and T.J. Tanaka, Pulsed plasma source spectrometry in the 80-800-eV x-ray region; Rev. Sci. Instrum. 54,10,1983.

seconds, then 5 minutes in Kodak "Rapid fix" ending the process with a 10 minute wash before drying.

Specular density measurements were obtained by scanning the Bragg reflected line spectra and background for each exposure. The instrument used was a Photometric Data System Model 1010A microdensitometer with a $100\mu\text{M}^2$ aperture. A numerical aperture (NA) of 0.1 was used for both the illumination and objective lenses of the microdensitometer. The microdensitometer outputs were digitized and filed in appropriate format for computer analysis.

Results:

A constant film-fog background, determined by examination of the total exposure set, was subtracted from the measured densities to yield a net specular density. These net densities and the corresponding exposures are tabulated in Table 2. For the iron and copper L emission lines, sub-level emissions are also noted. These data were grouped into a single file since the differences in emission energy are too small to produce density deviations of any significance.

Examples of the measured data are shown in Figures 1 and 2. Figure 1 illustrates the spectral measurements of the Cu L emission by the scanning proportional counter. For this measurement, the scan rate was $0.05^\circ/\text{step}$ with a net counting time of 1.7 seconds per step. Two film exposures, 90 minutes and 15 minutes, of the corresponding digitized film data are shown in Figures 2a and 2b. The low angular position ($\sim 58^\circ$) of the proportional counter place the measurement of the 4th order Bragg reflected Cu L α line in this example under suspicion. Therefore, all data related to this spectral line were rejected.

The densities and exposure intensities (photons per square micrometer) measured at each of the 6 energies are individually plotted in Figures 3 to 8. The solid curve plotted along with the measured points in each figure is a least square fit to the data using a 2nd order polynomial. Figure 9 shows the polynomial fits plotted collectively. These plots indicate a decrease in sensitivity as the energy is lowered from 1487 eV to 705 eV and further suggest a flat sensitivity dependence for energies lower than the iron emission at 705 eV. In order to substantiate this argument however, more data is needed for Oxygen and Carbon.

Figure 10 compares the Kodak 101-07 XUV measurement of Henke et al² at 1487 eV ($\text{Al}(\text{K}\alpha)$) to our measurement of the Kodak T max 100 XUV at the same energy. These measurements illustrate a similar response of the two films at this energy. The two measurements also imply that the sensitivities of the two films remain comparable in the sub-kilovolt region.

Acknowledgement:

We wish to thank Eric Frerking for furnishing and demonstrating the software used in making the plots for this report.

² B. L. Henke, F.G. Fujiwara, M.A. Tester, C.H. Dittmore, and M.A. Palmer, Low energy x-ray response of photographic films II Experimental characterization, *J. Opt. Soc. Am* 1,6, 1984.

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TABLE 1

ANODE				PROPORTIONAL COUNTER					
Material	Potential (kV)	Current (mA)	Fluorescent Radiation (Line)	Energy	Gas	Pressure (mm)	Volts	Window Material	Efficiency
Carbon	5.0	42	C (K α)	277 eV	C ₃ H ₈	200	1760	40 μ gm/cm ² Al + 50 μ gm /cm ² Polypropylene	0.8843
Al ₂ O ₃	7.0	"	O (K α)	525 eV	"	50	1050	"	0.9343
Fe	"	"	Fe (L)	705 eV	"	100	1250	"	0.9215
Cu	"	40	Cu (L)	930 eV	"	200	1650	"	0.9081
Mg	8.0	38	Mg (K α)	1254 eV	"	400	2200	1500 μ gm/cm ² Al	0.8732
"	"	39	"	"	"	760	2900	"	0.9802
Al	"	40	Al (K α)	1487 eV	P10	"	1700	"	0.9807
"	"	"	"	"	"	"	"	"	0.9807

Note: Analyzing Crystal - Lead Stearate, 2d=100 \AA

Pb-sta 2d spacing=100 \AA
Polypropylene (CH₂ = CH CH₃) x

TABLE 2

Photons				Specular				Photons				Specular				Photons			
Line	N	μM	Density	Line	N	μM	Density	Line	N	μM	Density	Line	N	μM	Density	Line	N	μM	Density
AL (K α)	10	0.06	0.10	AL (K α)	10	0.63	0.56	Cu L ()	$\alpha 6$	1.40	0.33	Fe L ()	$\alpha 4$	2.34	0.42	705 eV	$\alpha 4$	3.64	0.60
1487 eV	9	0.09	0.19	1487 eV	7	1.29	0.54	930 eV	$\alpha 5$	1.84	0.44	5/23/89	$\alpha 3$	4.21	0.55				
	8	0.10	0.10		8	1.53	0.62	4/6/89	$\alpha 6$	2.10	0.52		$\alpha 3$	5.81	0.73				
1/23/89	9	0.14	0.12	1/23/89	9	1.64	0.79		$\alpha 5$	2.20	0.37		$\alpha 5$	6.65	0.64				
	10	0.15	0.14		10	2.71	1.03		$\alpha 6$	2.33	0.37		$\alpha 3$	8.42	0.76				
	8	0.15	0.18		7	5.41	1.19		$\alpha 5$	2.81	0.49		$\alpha 4$	9.11	0.81				
	7	0.20	0.17		8	6.56	1.35		$\alpha 6$	3.68	0.62		$\alpha 5$	16.61	1.00				
	9	0.21	0.25		9	7.03	1.52		$\alpha 6$	4.19	0.74		$\alpha 3$	16.85	1.03				
	8	0.25	0.14		7	23.2	2.00		$\alpha 6$	4.21	0.89		$\alpha 3$	42.12	1.27				
	10	0.30	0.18		7	1.48	0.59		$\alpha 5$	6.98	0.92		$\alpha 3$			O (K α)	3	1.64	0.42
	9	0.36	0.27	Mg (K α)	6	1.52	0.61		$\alpha 5$	7.35	0.83					525 eV	3	9.84	0.79
	7	0.40	0.21	1254 eV		4.45	1.16		$\alpha 6$	8.39	0.96					5/9/89	3	27.1	1.13
	10	0.45	0.26	2/6/89	6	4.57	1.29		$\alpha 5$	11.03	1.05		$\alpha 3$			C (K α)	2	0.63	0.28
	8	0.51	0.29		7	8.89	1.34		$\alpha 6$	12.58	1.18					277 eV	2	1.26	0.29
	9	0.71	0.42		6	9.13	1.48		$\alpha 5$	13.97	1.10					5/4/89	2	2.52	0.51
	8	0.76	0.49		7	13.3	1.56		$\alpha 5$	27.94	1.38						2	3.78	0.62
	10	0.89	0.41		6	13.7	1.64		$\alpha 5$	41.90	1.58								
	7	0.99	0.39		5	0.67	0.25		$\alpha 4$	0.08	0.02								
	9	1.07	0.57		8	0.71	0.25	Fe L ()	$\alpha 3$	0.19	0.05								
	10	1.19	0.58		7	1.10	0.55	705 eV	$\alpha 4$	0.23	0.05								
	8	1.52	0.64		6	1.12	0.57		$\alpha 4$	0.30	0.08								
	7	1.98	0.71		5	1.33	0.46	5/23/89	$\alpha 4$	0.47	0.09								
	8	2.02	0.81		7	2.19	0.81		$\alpha 5$	0.55	0.11								
	9	2.14	0.87		8	2.25	0.89		$\alpha 3$	0.58	0.12								
	9	2.85	1.07		5	10.7	1.39		$\alpha 4$	0.91	0.19								
	7	2.97	0.88		7	17.6	1.80		$\alpha 4$	0.93	0.16								
	7	5.93	1.27		6	18.0	1.93		$\alpha 3$	1.16	0.25								
	7	7.91	1.46	Cu L ()	$\alpha 5$	0.55	0.14		$\alpha 3$	1.40	0.25								
	10	0.15	0.30	930 eV	$\alpha 5$	0.61	0.21		$\alpha 5$	1.66	0.27								
2/17/89	8	0.36	0.37	4/6/89	$\alpha 6$	0.70	0.19		$\alpha 4$	1.82	0.35								
	9	0.39	0.38		$\alpha 5$	1.10	0.36		$\alpha 3$	2.33	0.53								

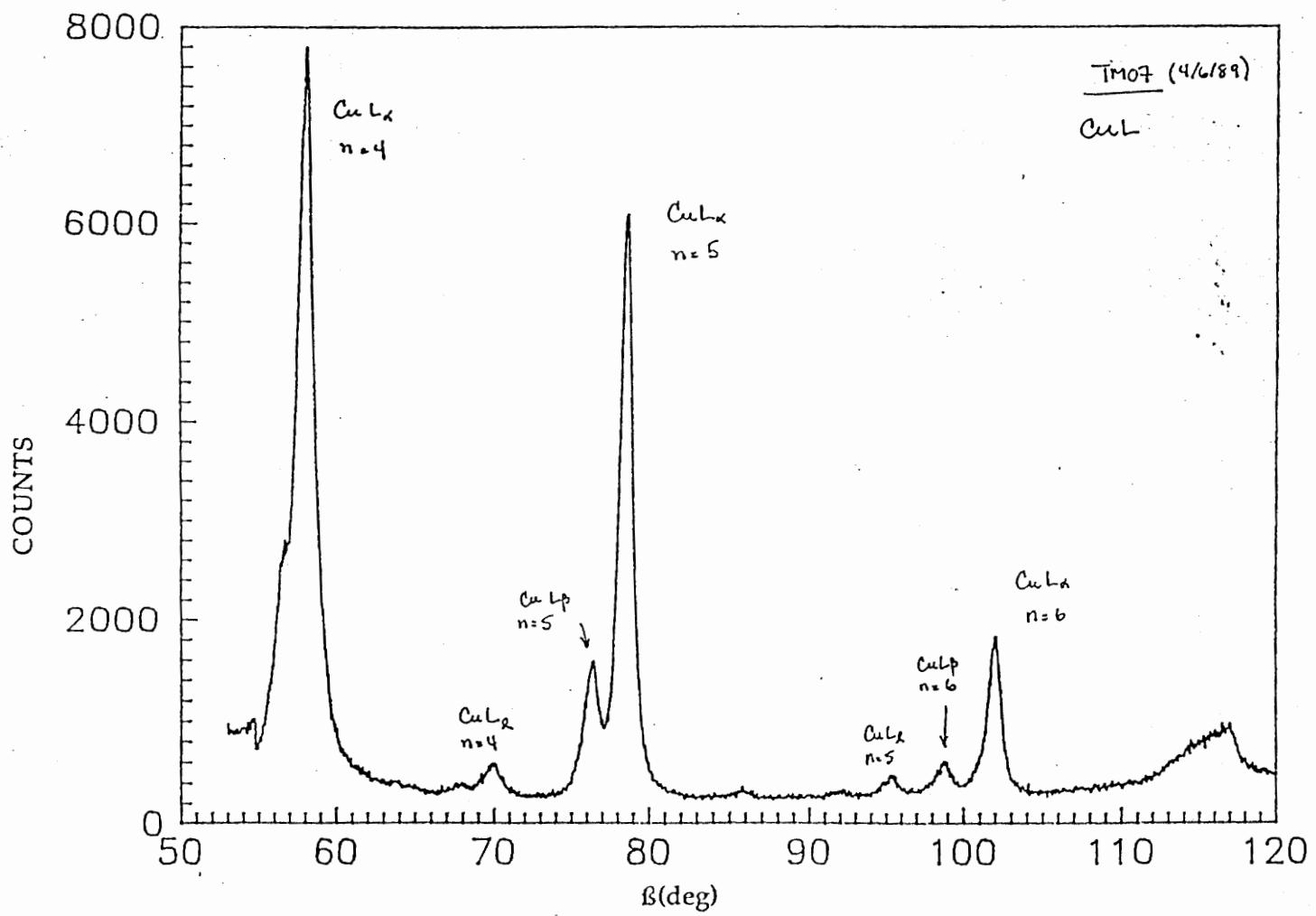


Figure 1
Spectral emission of Cu(L) line, measured by
the proportional counter scan.

files 4691a

T-MAX 100UV

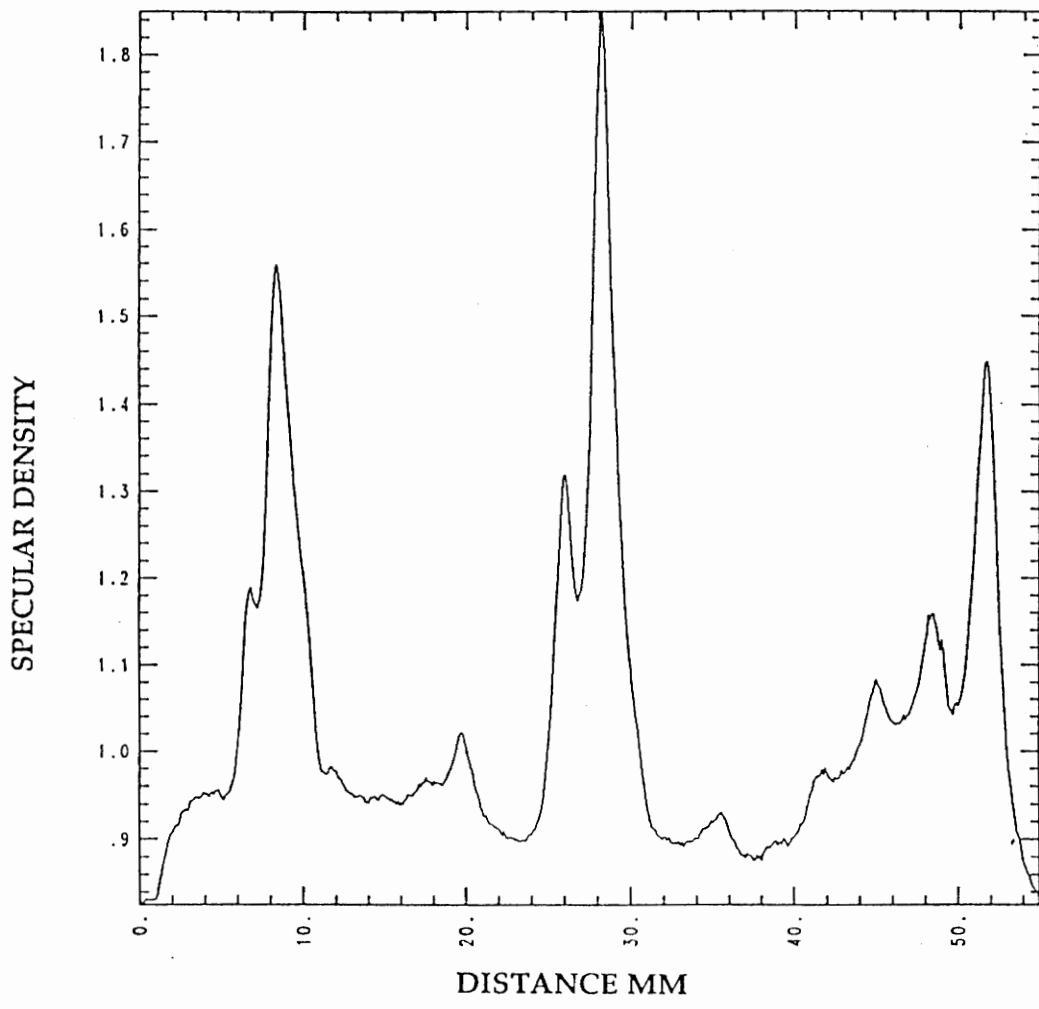


Figure 2a
Microdensitometer record of Bragg
reflected emission of Cu(L) line.
(90 minute exposure)

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T-MAX 100UV

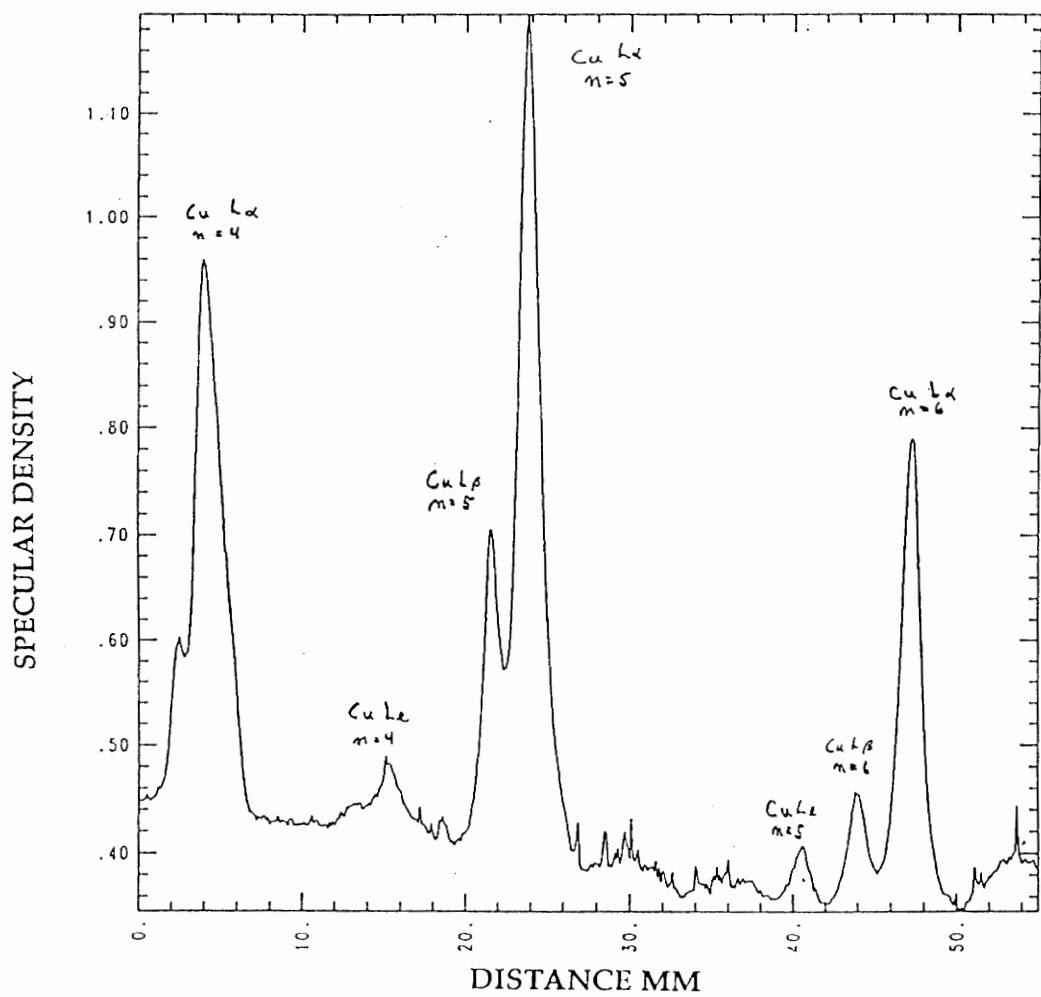


Figure 2b
Microdensitometer record of Bragg
reflected emission of Cu(L) line.
(15 minute exposure)

foreground: al0123p

background: al0123pfit

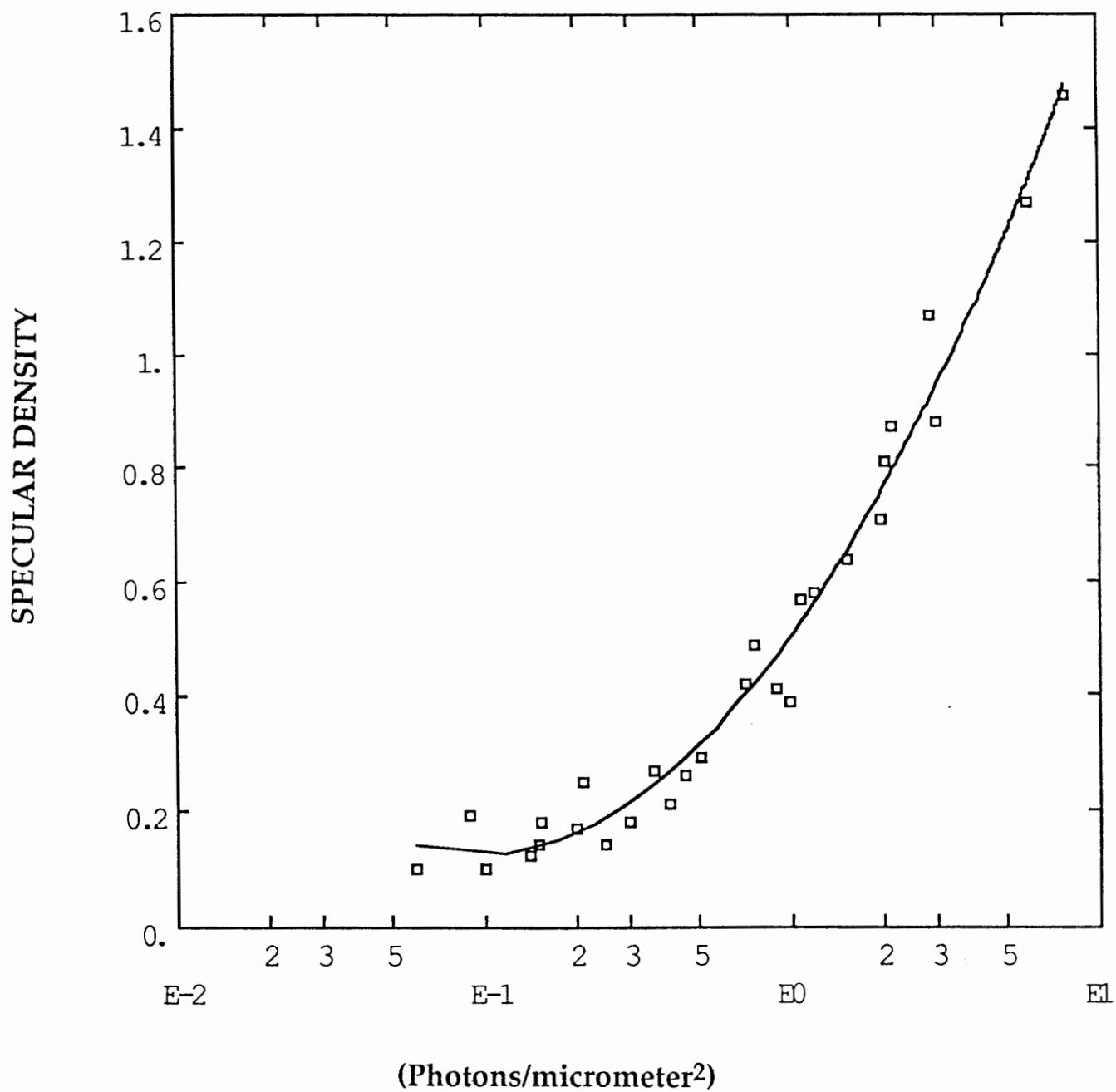


Figure 3
Al (K α); 1487 eV

foreground: mg0209a

background: mg0209afit

SPECULAR DENSITY

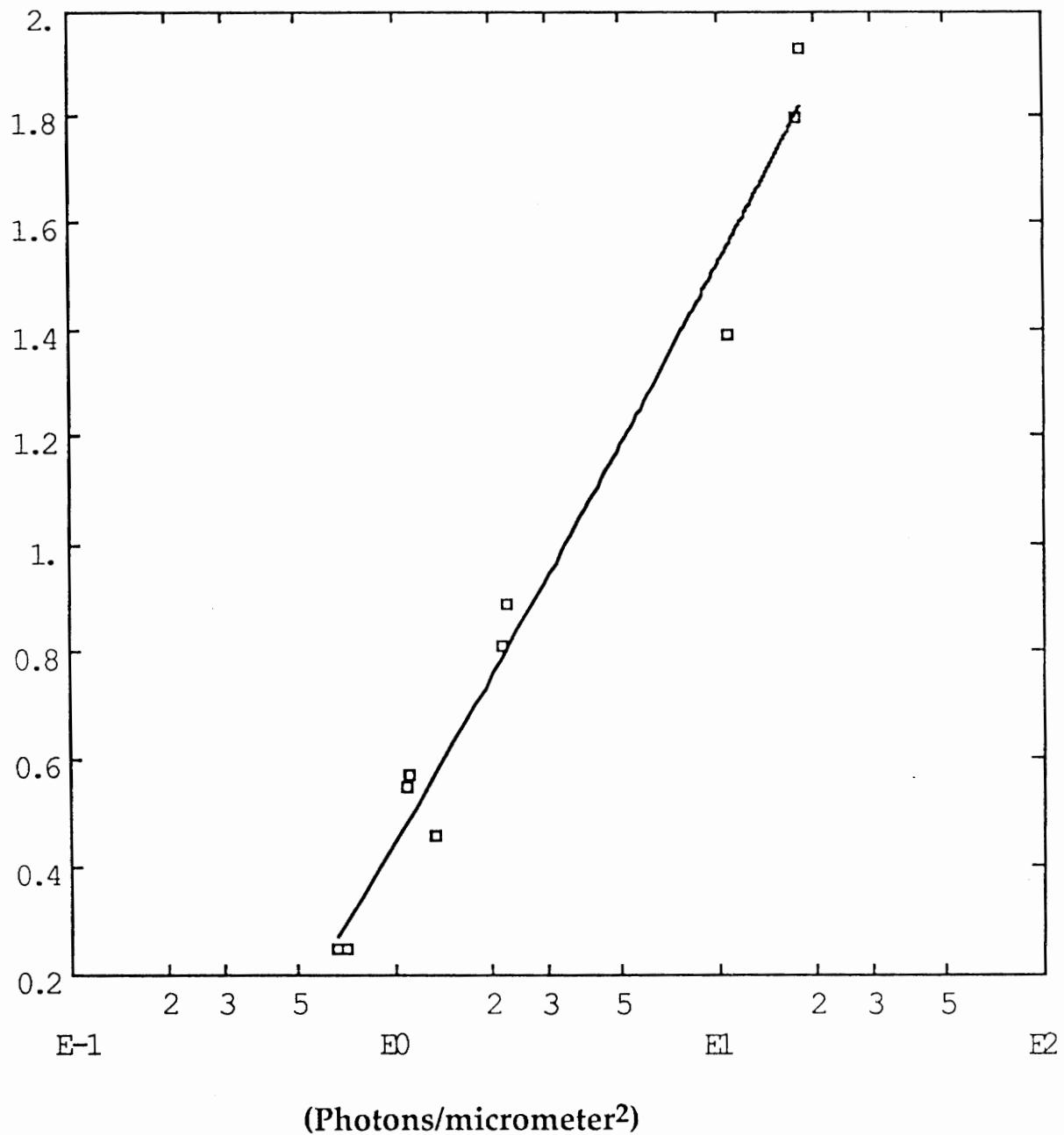


Figure 4
Mg (K α); 1254 eV

foreground: cu0406b

background: cu0406fit

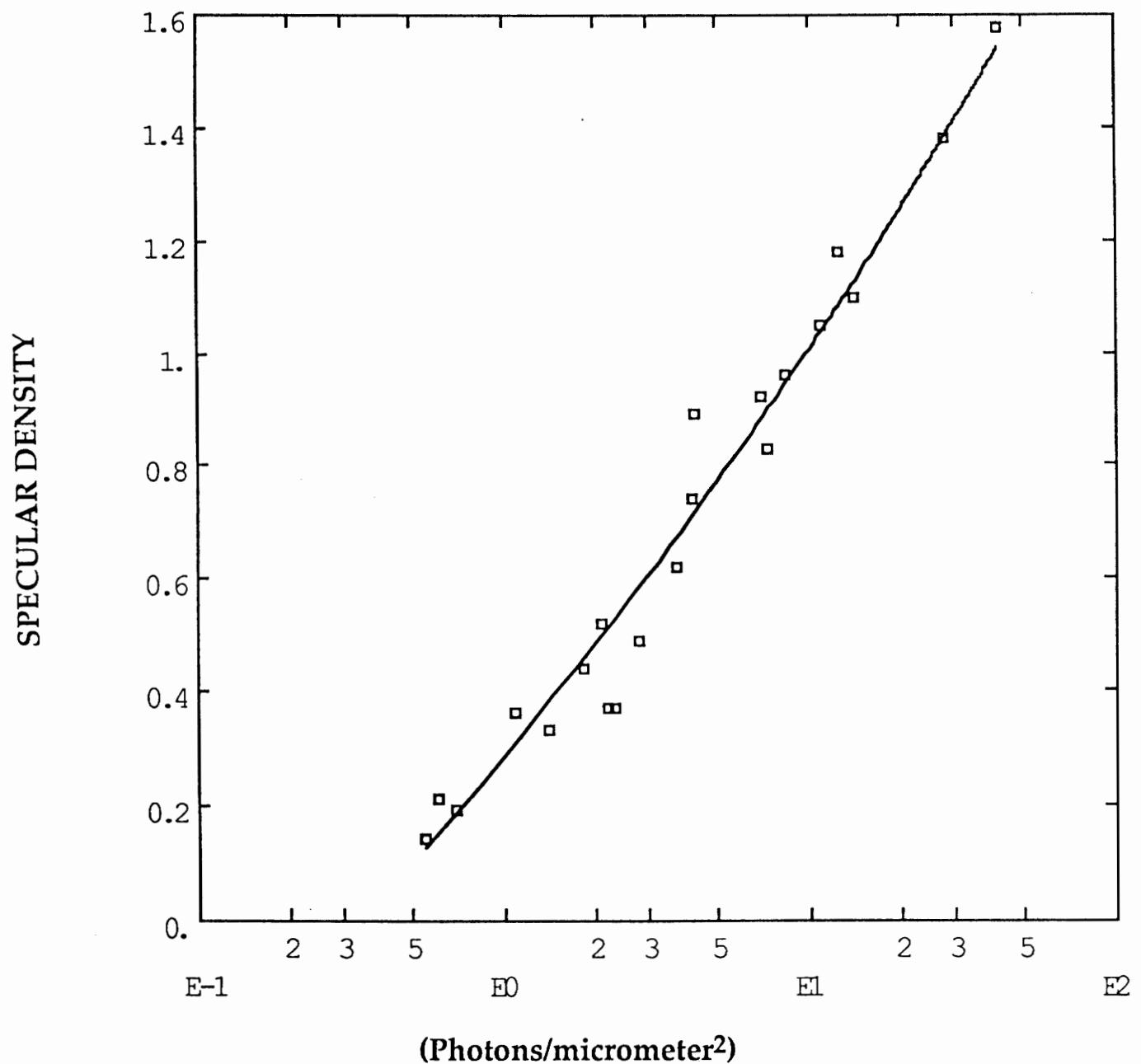


Figure 5
Cu (L); 930 eV

foreground: fe0523a

background: fe0523afit

SPECULAR DENSITY

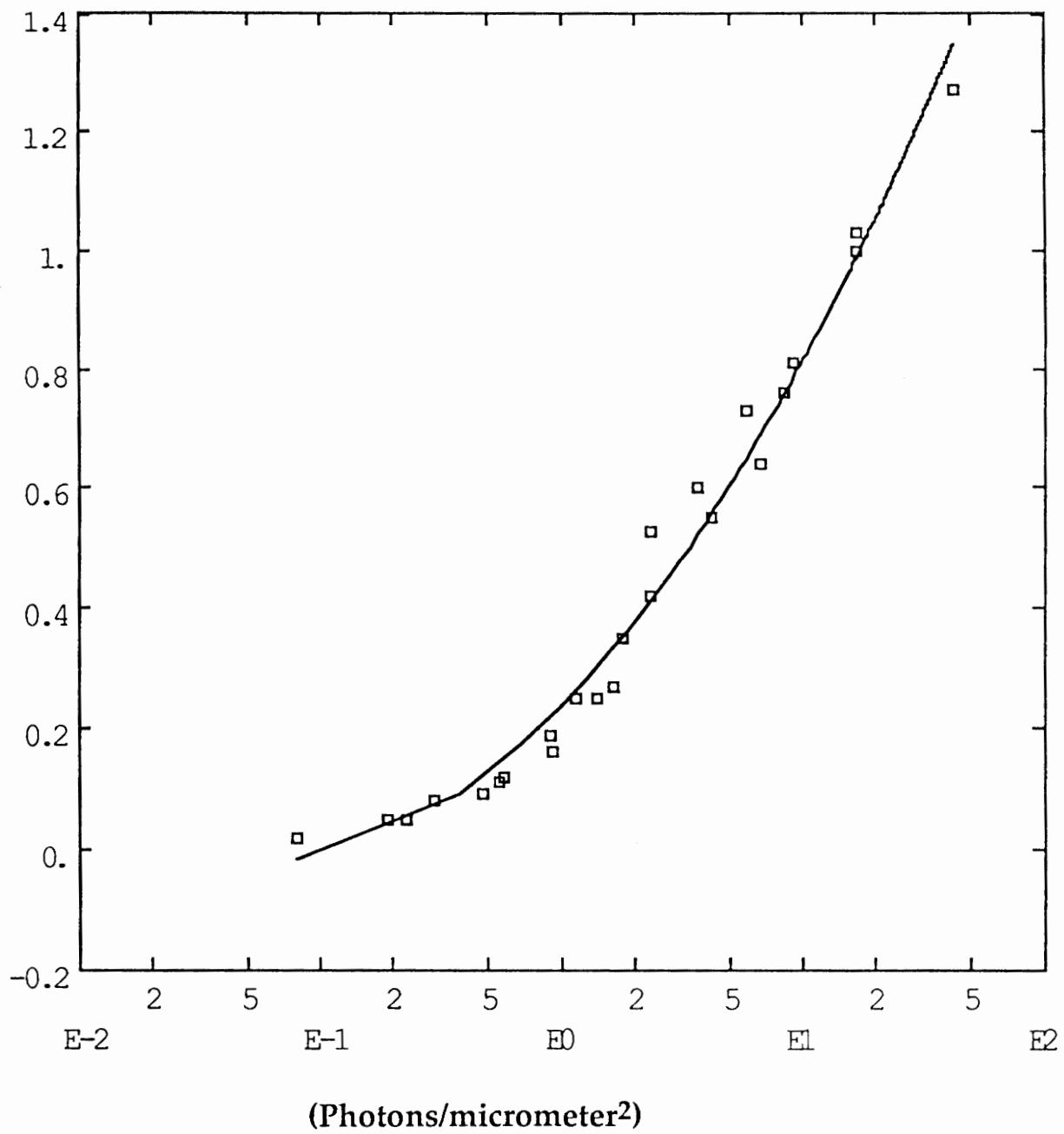


Figure 6
Fe (L); 705 eV

foreground: oo0509b

background: oo0509bfit

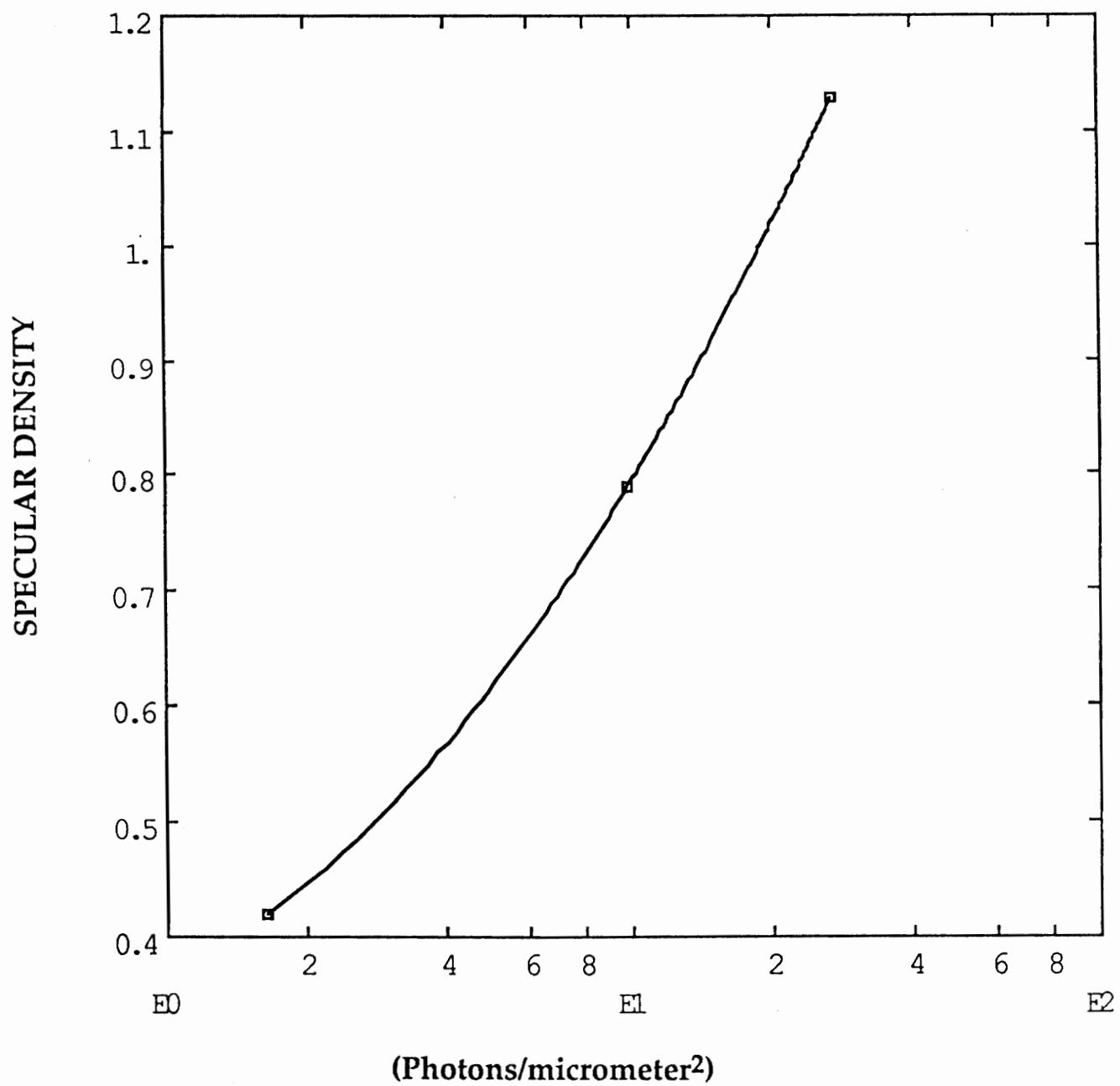
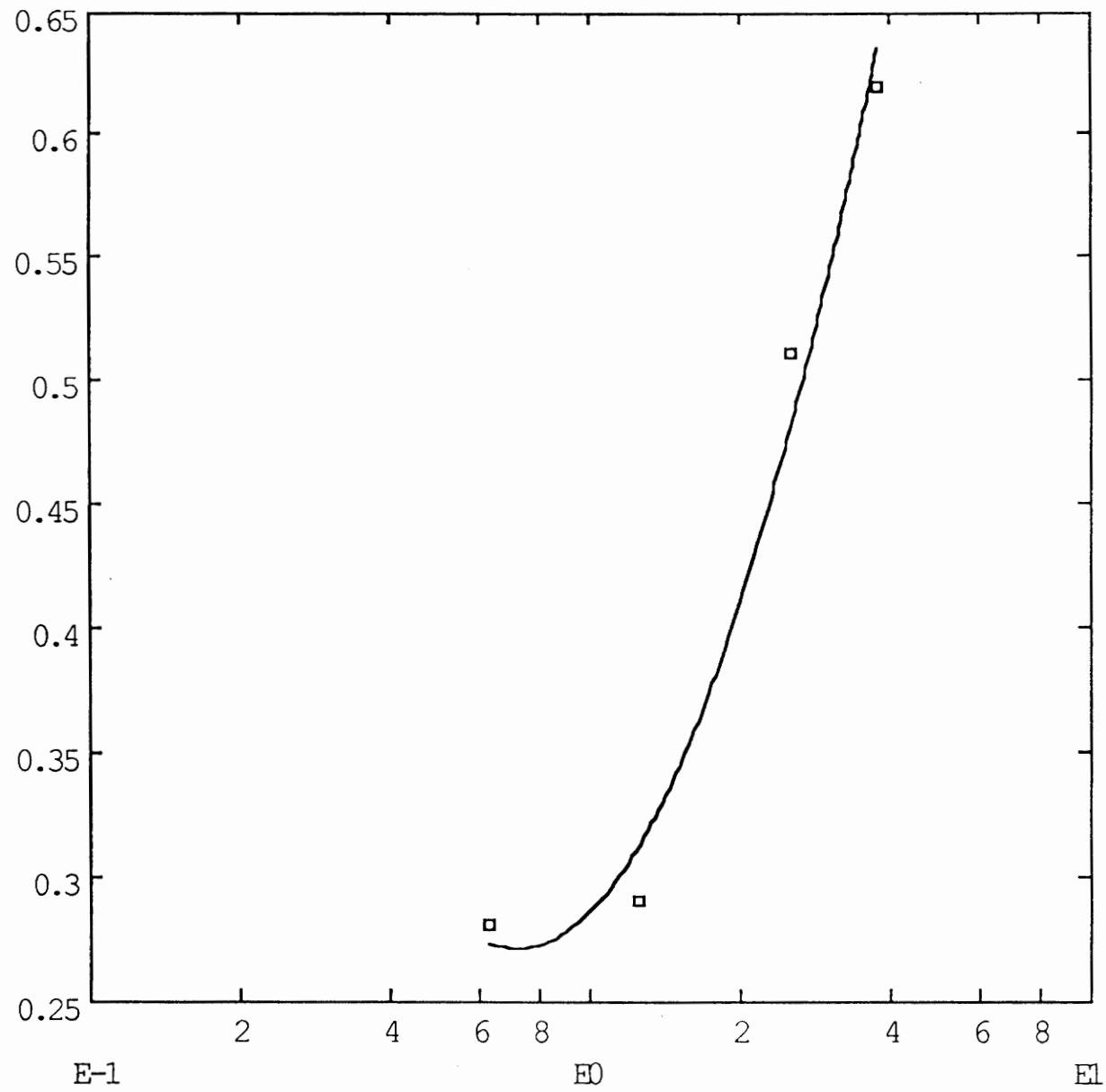


Figure 7
O (K α); 525 eV

foreground: cc0504a

background: cc0504afit

SPECULAR DENSITY



(Photons/micrometer²)

Figure 8
C (K α); 277 eV

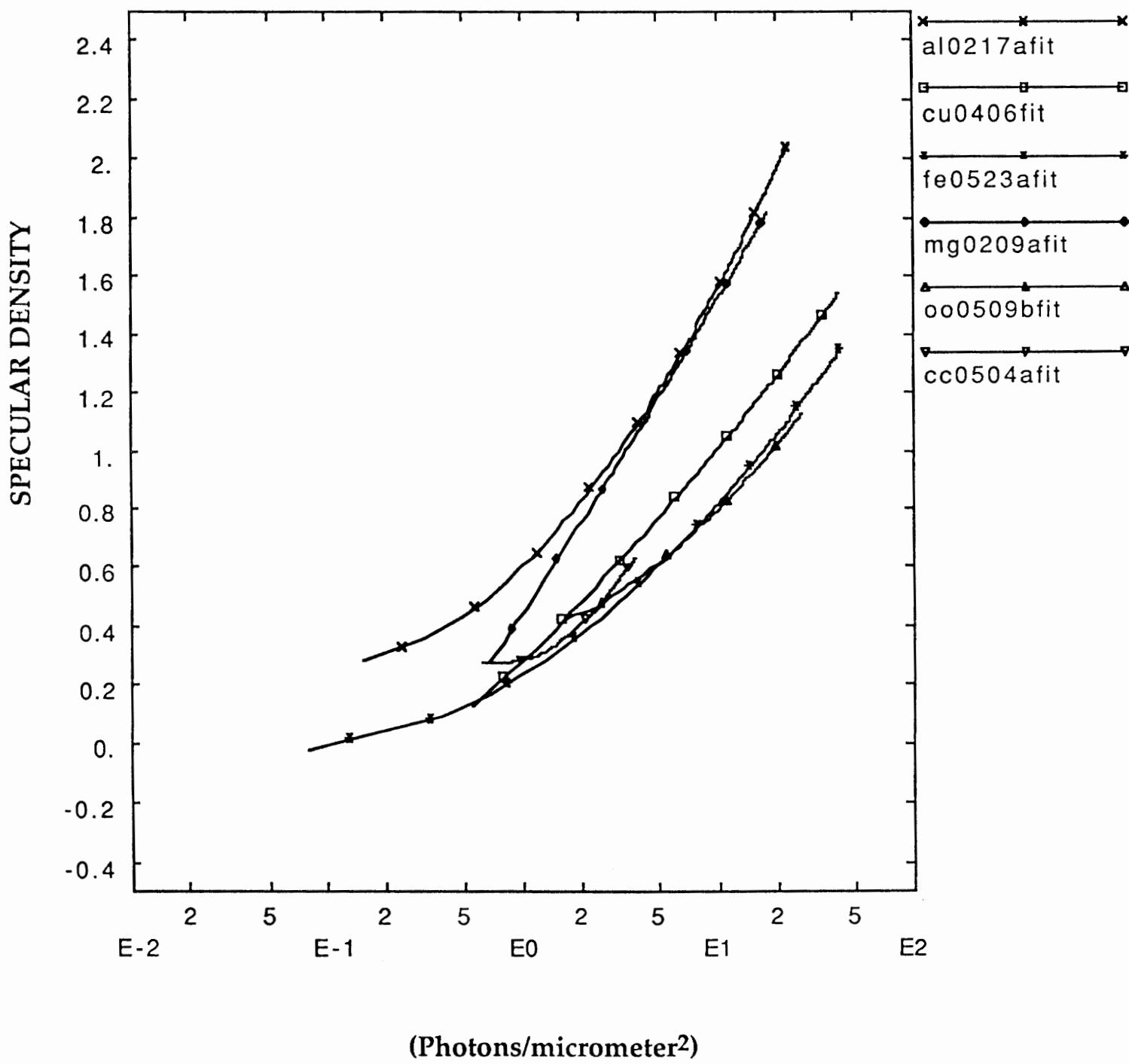


Figure 9
Polynomial fits to measured data

foreground: al101-07

background: al10123pfit

SPECULAR DENSITY

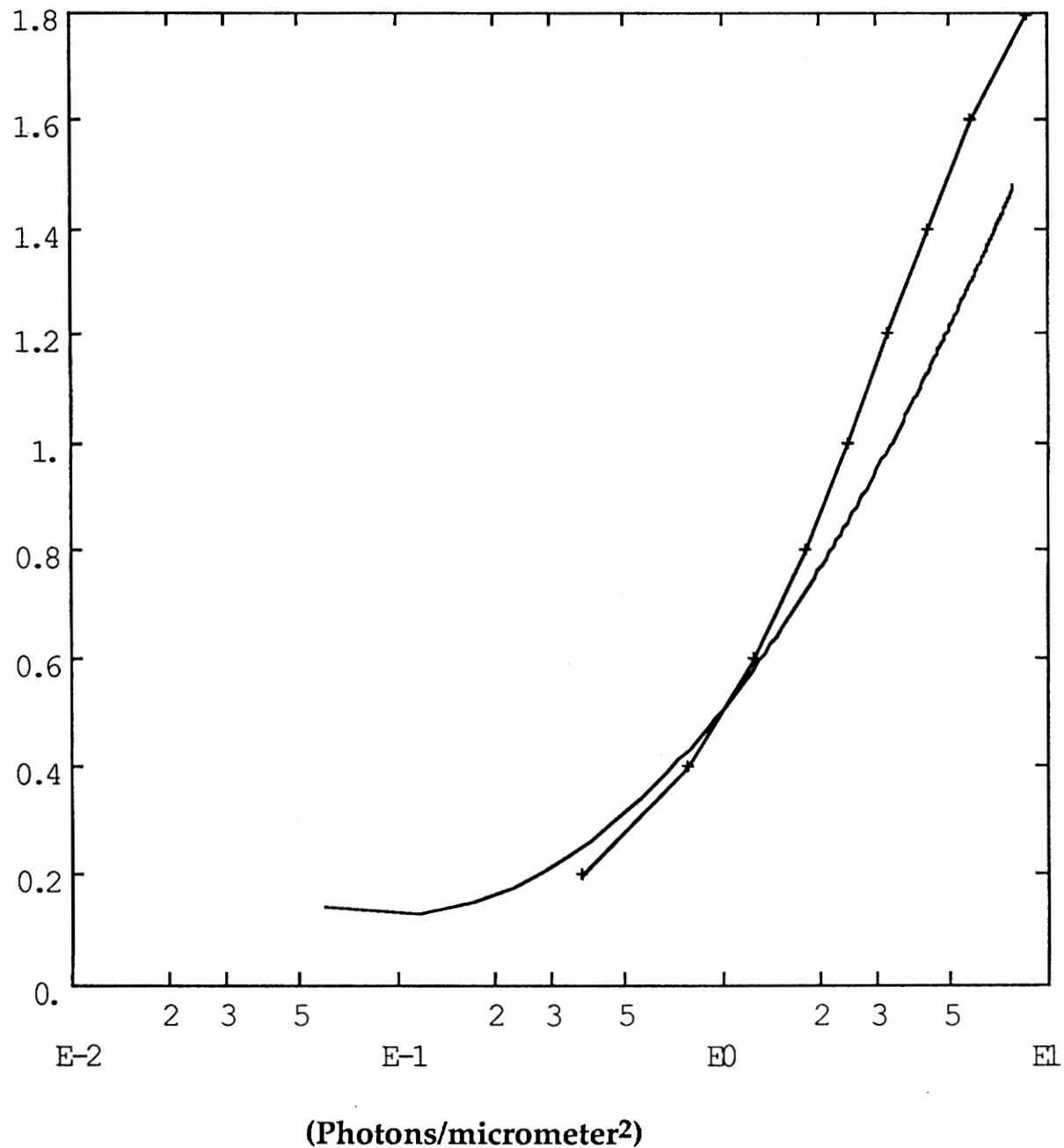


Figure 10
101-07 (+) compared to T max 100 at 1487 eV (Al (K α))

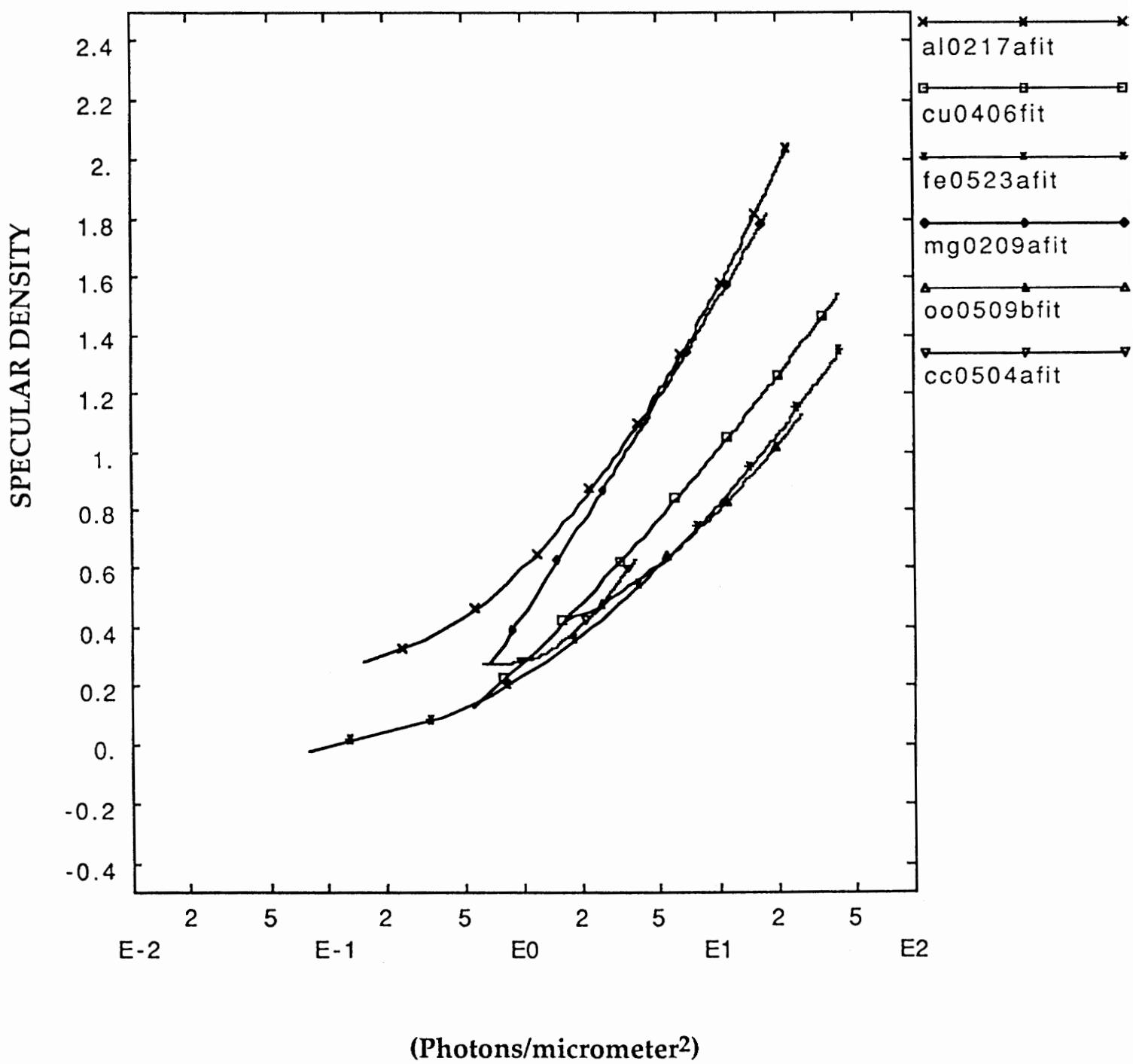


Figure 9
Polynomial fits to measured data

foreground: al101-07

background: al0123pfit

SPECULAR DENSITY

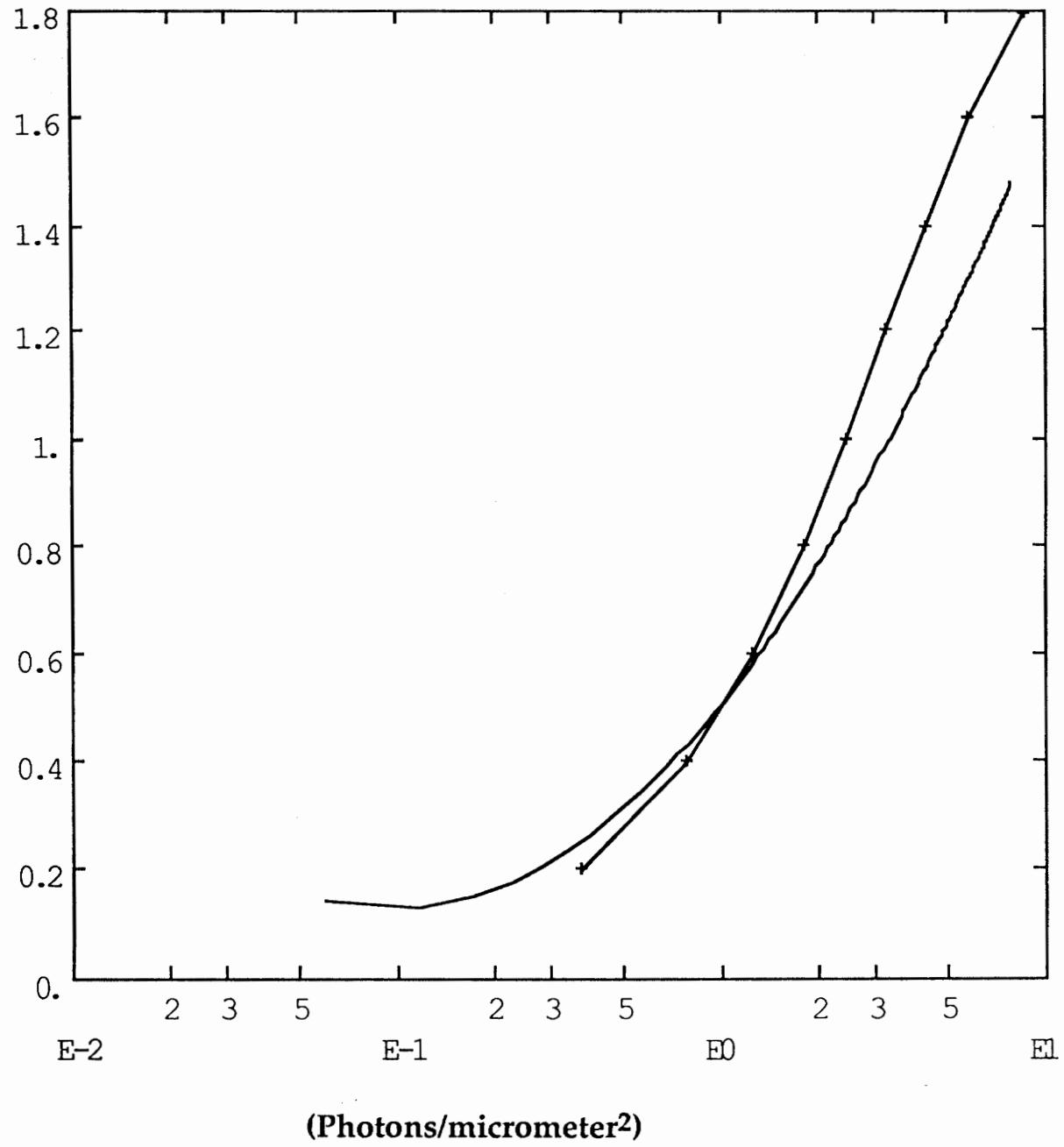


Figure 10
101-07 (+) compared to T max 100 at 1487 eV (Al (K α))